



The Fine Line: Summer 2015 Videos for the eBeam Community

Shot Talk - A Word from Our Sponsor

Aki Fujimura, CEO of D2S, sums up the hot topics at Photomask Japan—including EUV progress and VSB thermal effect correction with GPU acceleration—as well as highlights of the eBeam Initiative workshop before looking ahead to BACUS and the 4th annual eBeam Initiative survey.



Video Archive The Fine Line Spring Edition



Shot Talk: Aki Fujimura of D2S

Tech Talk

Noriaki Nakayamada of NuFlare Technology describes how NuFlare and D2S jointly conquer the menace of resist heating effects in VSB mask writing leveraging GPU acceleration, and offers a glimpse ahead at the future of multi-beam mask writing.



Tech Talk:
Takayuki Nakamura, Advantest

Perspective

Industry luminary Dr. David Lam of Multibeam Corporation provides an update on complementary eBeam lithography (CEBL)—including what's driving the need for CEBL, current and future applications, and progress toward implementation.



Perspective:
Colin Harris, PMC-Sierra

To unsubscribe, email requests@ebeam.org

[Click to view our entire video library](#)

The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please e-mail requests@ebeam.org or visit www.ebeam.org